

## UTILITIES TRANSFER SYSTEM IN A LITHOGRAPHY SYSTEM

### ABSTRACT OF THE DISCLOSURE

Techniques for transferring utilities to and from a reticle or wafer stage in a  
5 lithography system while minimizing physical disturbances that affect the stage are  
described. These techniques involve transferring utilities to and from the stage without  
making physical contact with the stage. Alternatively, utilities are transferred by making  
physical contact with the stage while the stage is in a stationary position. In addition to  
transferring utilities to and from the stage, devices such as processing devices, buffers  
10 (storage mediums), electrical components, and mechanical components can be placed  
within the stage to use and/or control the transferred utilities.